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(21) International Application Number: PCT/US91/01069 (22) International Filing Date: 25 February 1991 (25.02.91) (30) Priority data: 507,337 10 April 1990 (10.04.90) US (71) Applicant: E.I. DU PONT DE NEMOURS AND COMPANY [US/US]; 1007 Market Street, Wilmington, DE 19898 (US). (72) Inventors: BAUER, Richard, Douglas ; 102 Manor Drive, Kennett Square, PA 19348 (US). CHEN, Gwendyline, Yuan, Yu ; 106 Hickory Spring Road, Wilmington, DE 19807 (US). HERTLER, Walter, Raymond ; 1375 Parkersville Road, Kennett Square, PA 19348 (US). WHELAND, Robert, Clayton ; 510 Twaddell Mill Road, Wilmington, DE 19807 (US).		(74) Agents: SIEGELL, Barbara, C. et al.; E.I. du Pont de Nemours and Company, Legal/Patent Records Center, 1007 Market Street, Wilmington, DE 19898 (US). (81) Designated States: AT (European patent), BE (European patent), CA, CH (European patent), DE (European patent), DK (European patent), ES (European patent), FR (European patent), GB (European patent), GR (European patent), IT (European patent), JP, KR, LU (European patent), NL (European patent), SE (European patent). Published <i>With international search report.</i>
(54) Title: POSITIVE WORKING RESIST COMPOSITIONS AND THEIR UTILITY IN DRY FILM PHOTORESISTS (57) Abstract This invention relates to positive working resist compositions having utility in dry film photoresists and to fully aqueous methods for developing and stripping them. This Sheet Has Been Replaced 		